Micropatterning Japan TC
Meeting Summary and Minutes

SEMI Japan Standards Summer 2015 Meetings
Thursday, June 25, 2015, 16:00-18:00
SEMI Japan, Tokyo, Japan

Next Committee Meeting
SEMI Japan Standards Fall 2015 Meetings
Thursday, October 15, 2015, 15:30-17:00
SEMI Japan, Tokyo, Japan

Table 1 Meeting Attendees
Co-Chairs: Morihisa Hoga (Dai Nippon Printing)
SEMI Staff: Junko Collins (SEMI Japan)

<table>
<thead>
<tr>
<th>Company</th>
<th>Last</th>
<th>First</th>
<th>Company</th>
<th>Last</th>
<th>First</th>
</tr>
</thead>
<tbody>
<tr>
<td>Dai Nippon Printing</td>
<td>Hoga</td>
<td>Morihisa</td>
<td>Dai Nippon Printing</td>
<td>Suzuki</td>
<td>Toshio</td>
</tr>
<tr>
<td>-</td>
<td>Otaki</td>
<td>Masao</td>
<td>SEMI Japan</td>
<td>Collins</td>
<td>Junko</td>
</tr>
</tbody>
</table>

Table 2 Leadership Changes
None

Table 3 Ballot Results
None

Table 4 Authorized Ballots

<table>
<thead>
<tr>
<th>#</th>
<th>When</th>
<th>SC/TF/WG</th>
<th>Details</th>
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</thead>
<tbody>
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None

Table 5 Authorized Activities

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<tr>
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<th>Type</th>
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<th>Details</th>
</tr>
</thead>
<tbody>
<tr>
<td>5484</td>
<td>Discontinued</td>
<td></td>
<td>SNARF  Revision to SEMI P22-0307, Guideline for Photomask Defect Classification and Size Definition.</td>
</tr>
<tr>
<td>5537</td>
<td>Discontinued</td>
<td></td>
<td>SNARF  Line Item Revision to SEMI P23-0200 (Reapproved 1107), Guidelines for Programmed Defect Masks and Benchmark Procedures for Sensitivity Analysis of Mask Defect Inspection System</td>
</tr>
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</table>

Table 6 New Action Items

<table>
<thead>
<tr>
<th>Item #</th>
<th>Assigned to</th>
<th>Details</th>
</tr>
</thead>
<tbody>
<tr>
<td>MP150625-1</td>
<td>Toshio Suzuki</td>
<td>Submit 5229A to Cycle 6 by Suzuki-san</td>
</tr>
</tbody>
</table>
1 Welcome, Reminders and Introductions
Morihisa Hoga, committee co-chair, called the meeting to order at 16:00. Self-introductions were made followed by the agenda review.

2 Required Meeting Elements
The meeting reminders on program membership requirement, antitrust issues, intellectual property issues and international effective meeting guidelines, were reviewed by SEMI staff, Junko Collins.

3 Review of Previous Meeting Minutes
The committee reviewed the minutes of the previous meeting held on January 29, 2015.

Motion: To approve the minutes of the previous meeting as submitted.
By / 2nd: Toshio Suzuki (Dainippon Printing) / Masako Otaki (-)
Discussion: None
Vote: 2 in favor and 0 opposed. Motion passed.

4 SEMI Staff Report

Attachment: SEMI Staff Report 2015 June R0.2

5 Liaison Reports
5.1 Microlithography North America TC Report
Junko Collins reported as following.
The NA Microlithography committee has not met since SEMICON West 2013.
One of the co-chairs Rick Silver will be replaced by Bryan Barnes. He will be attending the meetings at West including the NARSC. Our first order of business is to bring several outdated Standards up to date. There is also a P5 revision activity to be approved at West. This is being driven by John Zimmerman, a TF leader from ASML.
Next meeting is scheduled on July 14, Tuesday 10:00-12:00 during SEMICON West.

Attachment: No attachment

6 Task Force Reports
6.1 Mask Data Format for Mask Tools Task Force
Toshio Suzuki reported for the Mask data Format for Mask Tools Task Force. Of note:
- Doc. #5229A, Revision to SEMI P44-0211, Specification for Open Artwork System interchange Standard (OASIS®) Specific to Mask Tools., will be submitted for cycle 6.
6.2 5 Year Review Task Force

Masao Otaki reported on progress for the 5 Year Review Task Force. Of note:

- The Task Force proposes to discontinue the following SNARFs. Task Force discussed whether revise the document is better or put these documents under inactive status and chose inactive status.
  - Doc.#5484, Revision to SEMI P22-0307, Guideline for Photomask Defect Classification and Size Definition.
  - Doc.#5537, Line Item Revision to SEMI P23-0200 (Reapproved 1107), Guidelines for Programmed Defect Masks and Benchmark Procedures for Sensitivity Analysis of Mask Defect Inspection System

Motion: To discontinue and withdraw SNARF 5484, because the current P22-0307 is in effect without any changes.

By / 2nd: Masako Otaki (-) / Toshio Suzuki (Dainippon Printing)

Discussion: None

Vote: 2 in favor and 0 opposed. Motion passed.

Motion: To discontinue and withdraw SNARF 5537, because the current P20-0200 is in effect without any changes.

By / 2nd: Masako Otaki (-) / Toshio Suzuki (Dainippon Printing)

Discussion: None

Vote: 2 in favor and 0 opposed. Motion passed.

7 Old Business

7.1 Previous Meeting Action Items

Junko Collins reviewed the previous meeting action items.

Table 7 Previous Meeting Actions Items

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<thead>
<tr>
<th>Item #</th>
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</table>
| MP120828-2 | 5 Year Review Task Force         | To draft the document of Doc. 5484, Revision to SEMI P22-0307 to submit it for the earliest possible cycle. … **Closed/Aborted**
|            |                                  | **SNARF 5484 was withdrawn at this meeting.**                            |
| MP121211-1 | 5 Year Review Task Force         | To draft the document of Doc. 5537, Line Item Revision to SEMI P23-0200 to submit it for the earliest possible cycle. … **Closed/Aborted**
|            |                                  | **SNARF 5537 was withdrawn at this meeting**                             |
| MP130828-1 | 5 Year Review Task Force         | To draft the background statements for the Document #5484 and #5537. … **Closed/Aborted**
|            |                                  | **SNARF 5484/5537 were withdrawn at this meeting**                      |

8 New Business

8.1 Standards Document Development Project Period

No related document for this time.

8.2 Disbandment of this TC chapter

Participants discussed about disbandment of this TC chapter in near future at this meeting. Due to lack of participants in the activities, it seems difficult to continue to manage the TC Chapter activities.

The TC Chapter also has judged there is no new topic for standardization regarding to micropattering.

Future plan for disbandment
9 Action Item Review

9.1 New Action Items

Junko Collins reviewed the new action items. These can be found in the New Action Items table at the beginning of these minutes.

Submit 5229A to Cycle 6 by Suzuki-san

10 Next Meeting and Adjournment

The next meeting of the Micropatterning Japan TC meeting is scheduled for Thursday, October 15, 2015, 15:30-17:00, at SEMI Japan, Tokyo, Japan.
Respectfully submitted by:
Junko Collins
Director, Standards & EHS
SEMI Japan
Phone: +81.3.3222.5819
Email: jcollins@semi.org

Minutes approved by:
Morihisa Hoga (Dai Nippon Printing), Co-chair

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<tr>
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<tbody>
<tr>
<td>1</td>
<td>SEMI Staff Report 2015 June R0.2</td>
</tr>
<tr>
<td>2</td>
<td>150604_All-Committee_Document-List</td>
</tr>
</tbody>
</table>

#1 Due to file size and delivery issues, attachments must be downloaded separately. A .zip file containing all attachments for these minutes is available at www.semi.org. For additional information or to obtain individual attachments, please contact Junko Collins at the contact information above.